

**Notice of References Cited**Applicant/Patent  
**CHEUNG et al**Application/Control No.  
**09/418,818**Examiner  
**Rudy Zervigon**Art Unit  
**1763**

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	<b>Document Number</b> Country Code-Number-Kind Code	<b>Date</b> MM-YYYY <sup>1</sup>	<b>Name</b>	<b>Classification<sup>2</sup></b>	
<b>A</b>	5,286,581	2/1994	Fourmun Lee	430	5
<b>B</b>					
<b>C</b>					
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<b>J</b>					
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<b>L</b>					
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**FOREIGN PATENT DOCUMENTS**

	<b>Document Number</b> Country Code-Number-Kind Code	<b>Date</b> MM-YYYY <sup>1</sup>	<b>Country</b>	<b>Name</b>	<b>Classification<sup>2</sup></b>	
<b>N</b>						
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<sup>\*</sup> A copy of this reference is not being furnished with this Office action. See MPEP § 707.05(a).<sup>1</sup> Dates in MM-YYYY format are publication dates.<sup>2</sup> Classifications may be U.S. or foreign.